AMENDMENTS TO THE SPECIFICATION

Page 12, please replace the third paragraph with the following amended paragraph:

One preferred embodiment of the method for manufacturing a sputtering target includes (1) ~~dissolving or~~ dispersing a silicon carbide powder and a carbon source into a solvent to manufacture a mixed powder in a slurry form, (2) pouring the resulting mixed powder into a mold and drying the same to obtain a green material, (3) calcinating the resulting green material at 1200 to 1800°C under a vacuum or inert gas atmosphere to obtain a calcined material, and (4) impregnating the resulting calcined material with molten metallic silicon due to capillary phenomenon to react free carbon in the above-described calcined material with the silicon aspirated into the above-described calcined material due to capillary phenomenon thereby to obtain a silicon carbide material. In the following, the above-described method for manufacturing a sputtering target will be described in detail in each step.

Page 13, please replace the first paragraph with the following amended paragraph:

A slurry-form mixed powder is manufactured by ~~dissolving or~~ dispersing a silicon carbide powder and a carbon source, in addition, an organic binder or a defoamer, if desired, into a solvent. When materials to be dissolved or dispersed are sufficiently agitated and admixed at the time of dissolving or dispersing these materials, pores can be uniformly dispersed into a green material.

Page 18, after the second paragraph, please insert:

Refractive indexes of covering layers formed on glass plates at the measured optical wavelength of 633 nm are 4.16 or less.

A volume resistivity of a covering layer formed on a glass plate is 3.0×10^3 (Ω·cm) or less.